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(12) **United States Design Patent**  
**Hawrylchak et al.**

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(54) **SHOWERHEAD FOR A SEMICONDUCTOR PROCESSING CHAMBER**

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(52) **U.S. Cl.**  
USPC ..... **D23/213**

(58) **Field of Classification Search**  
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CPC ..... C23C 16/45565; B05B 1/00; B05B 1/18; B05B 9/01  
See application file for complete search history.

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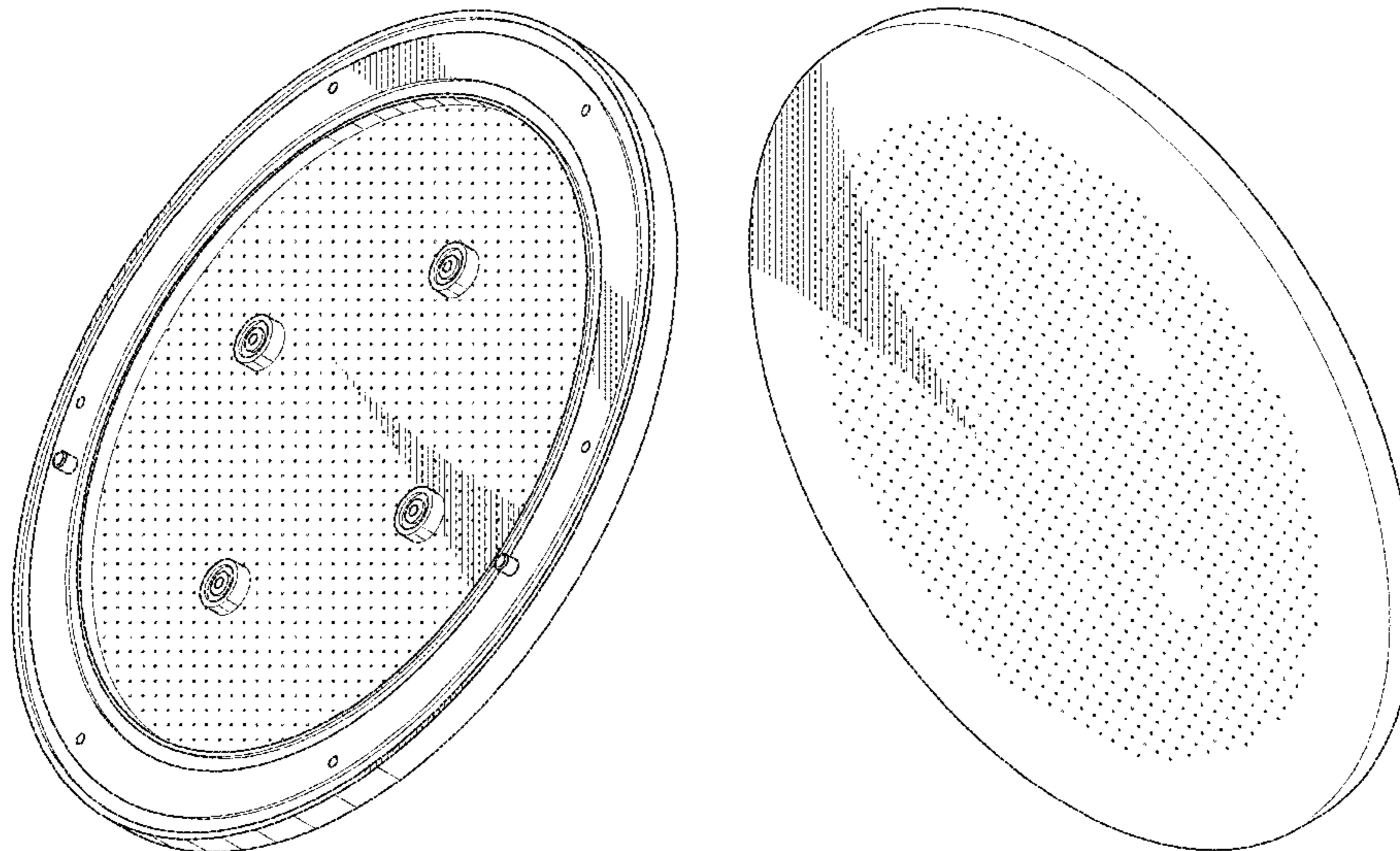
(57) **CLAIM**

The ornamental design for a showerhead for a semiconductor processing chamber, as shown and described.

**DESCRIPTION**

FIG. 1 is an isometric top view of a showerhead for a semiconductor processing chamber showing my new design. FIG. 2 is an isometric bottom view thereof. FIG. 3 is a top plan view thereof. FIG. 4 is a bottom plan view thereof. FIG. 5 is a front elevational view thereof indicated by lines 5-5 of FIG. 3, the rear elevational view being a mirror image. FIG. 6 is a side elevational view thereof indicated by lines 6-6 of FIG. 3, the opposite side elevational view being a mirror image. FIG. 7 is a cross-sectional view thereof taken along lines 7-7 of FIG. 3. FIG. 8 is a cross-sectional view thereof taken along lines 8-8 of FIG. 3. FIG. 9 is an enlarged view of a portion of FIG. 7. FIG. 10 is an enlarged view of another portion of FIG. 7; and, FIG. 11 is an enlarged view of a portion of FIG. 8.

**1 Claim, 8 Drawing Sheets**



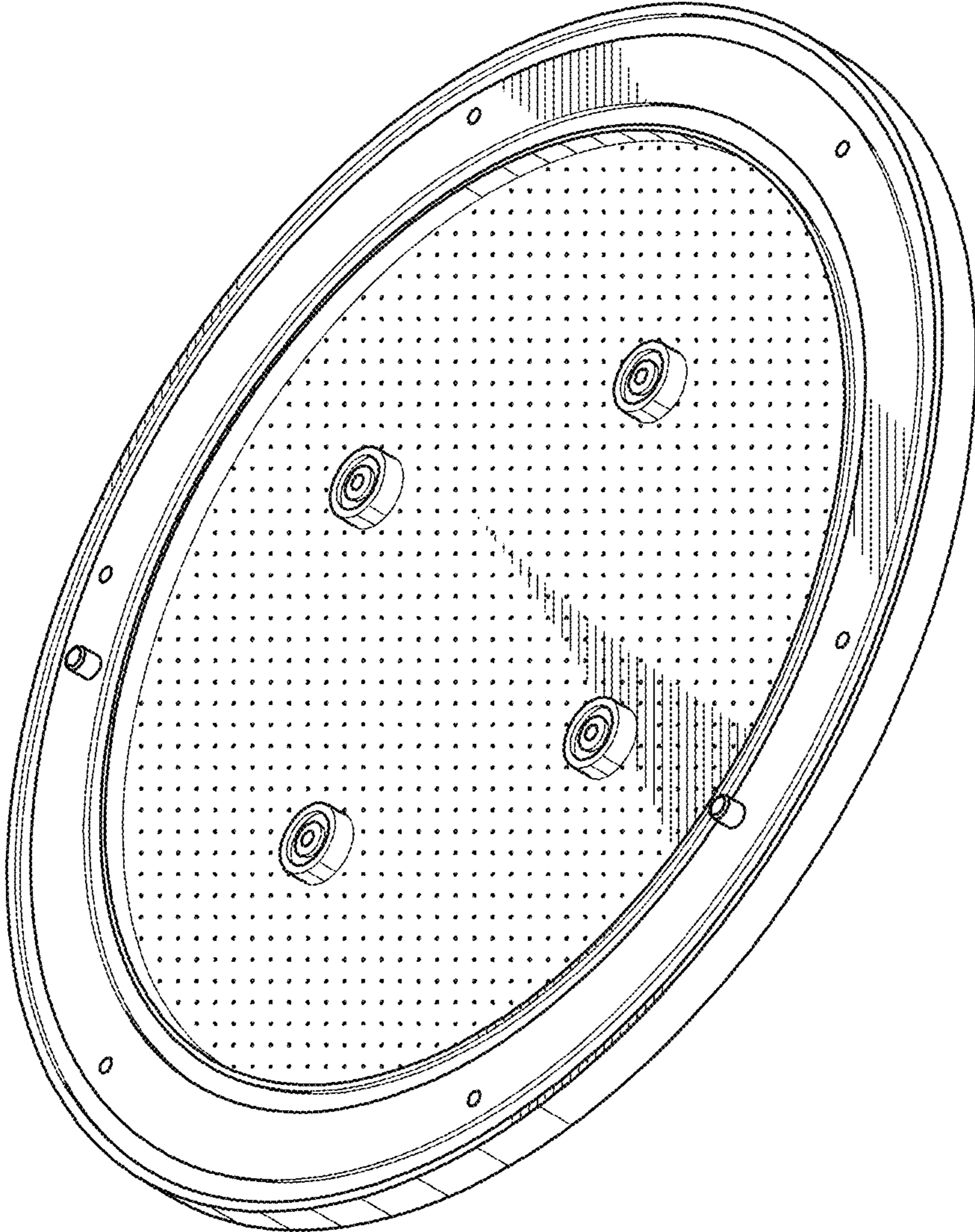
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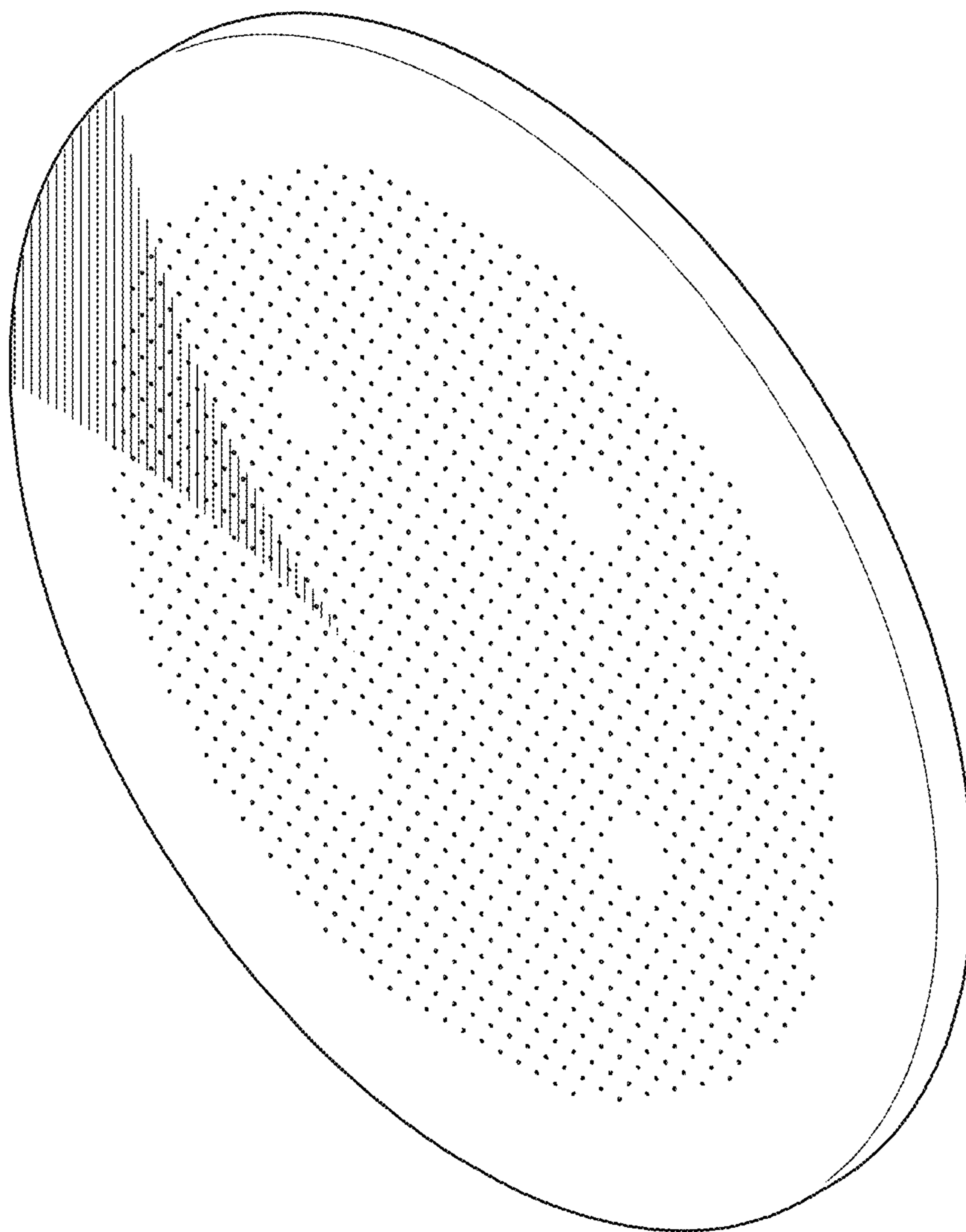
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*Fig. 1*



*Fig. 2*

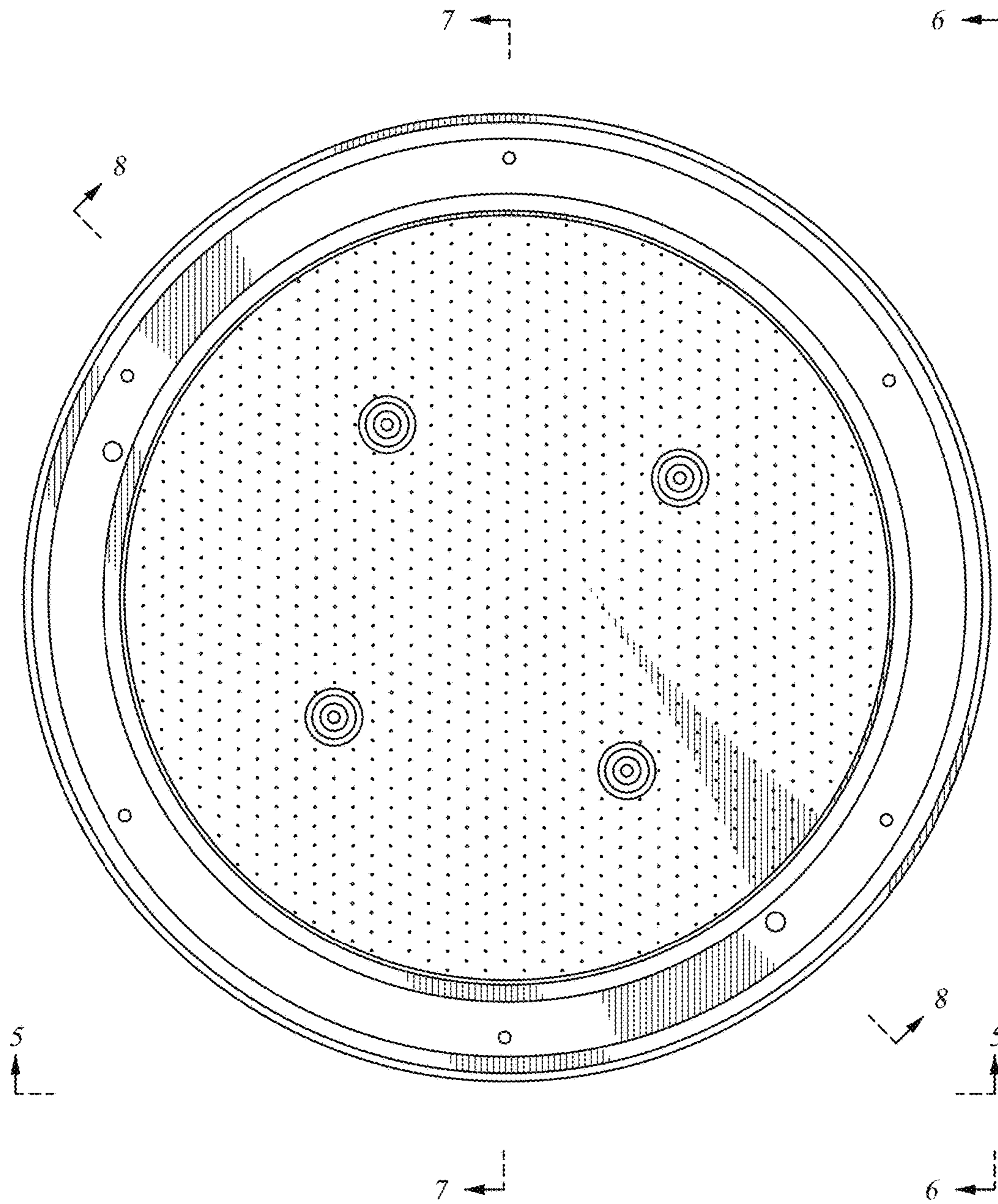
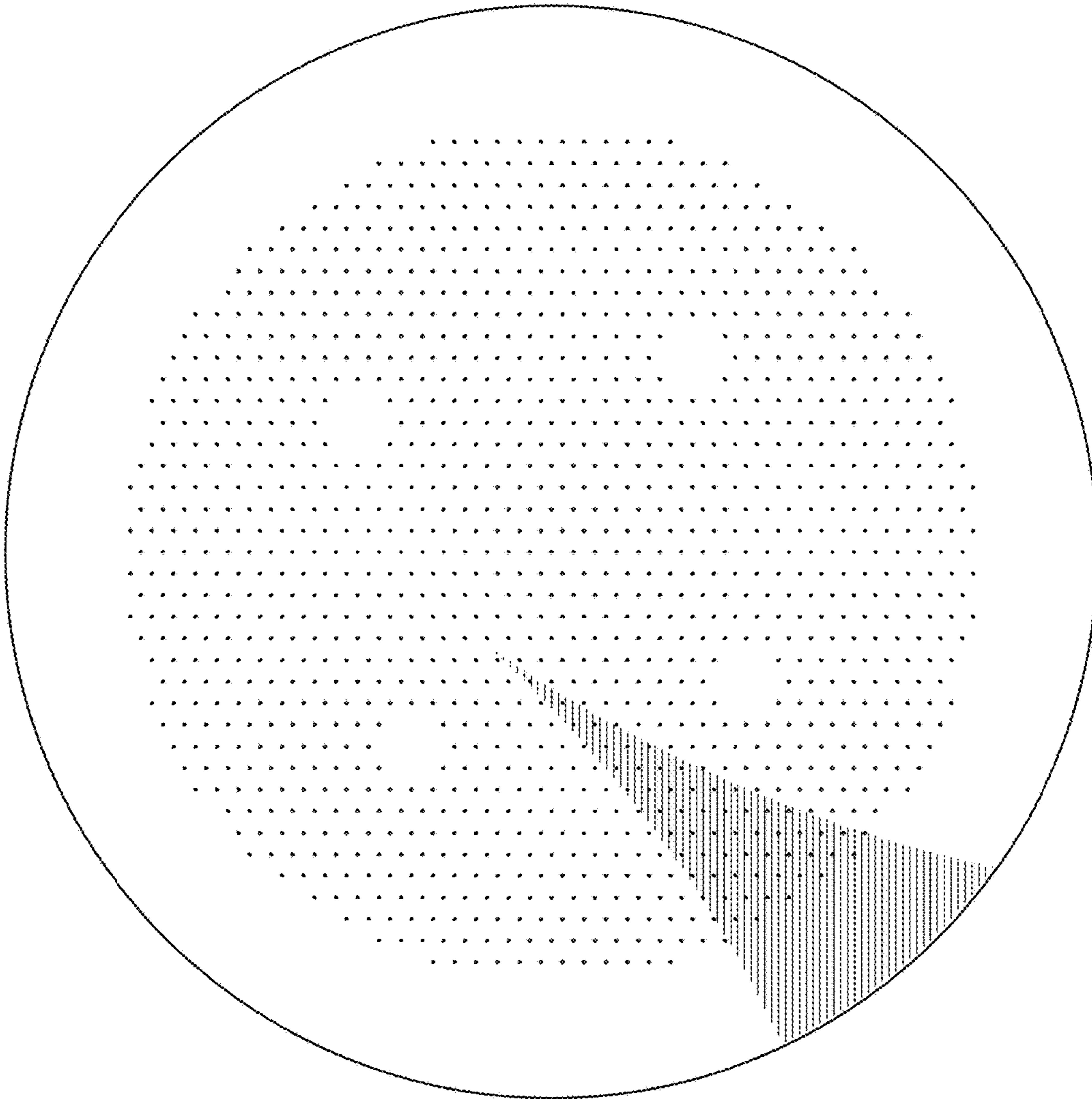


Fig. 3



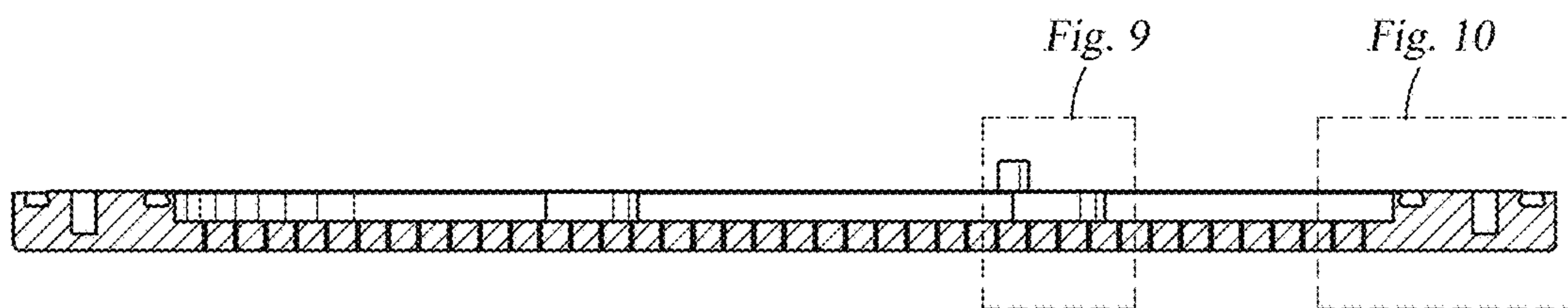
*Fig. 4*



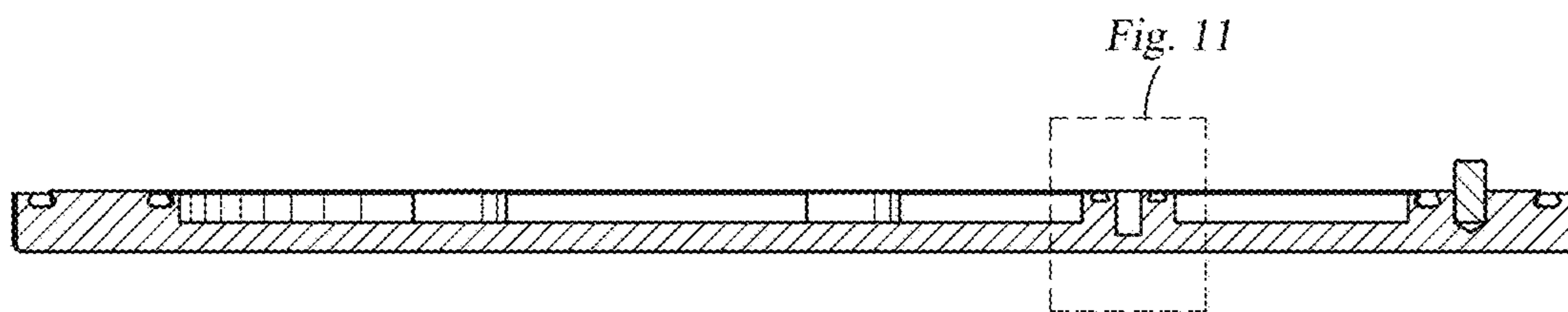
*Fig. 5*



*Fig. 6*

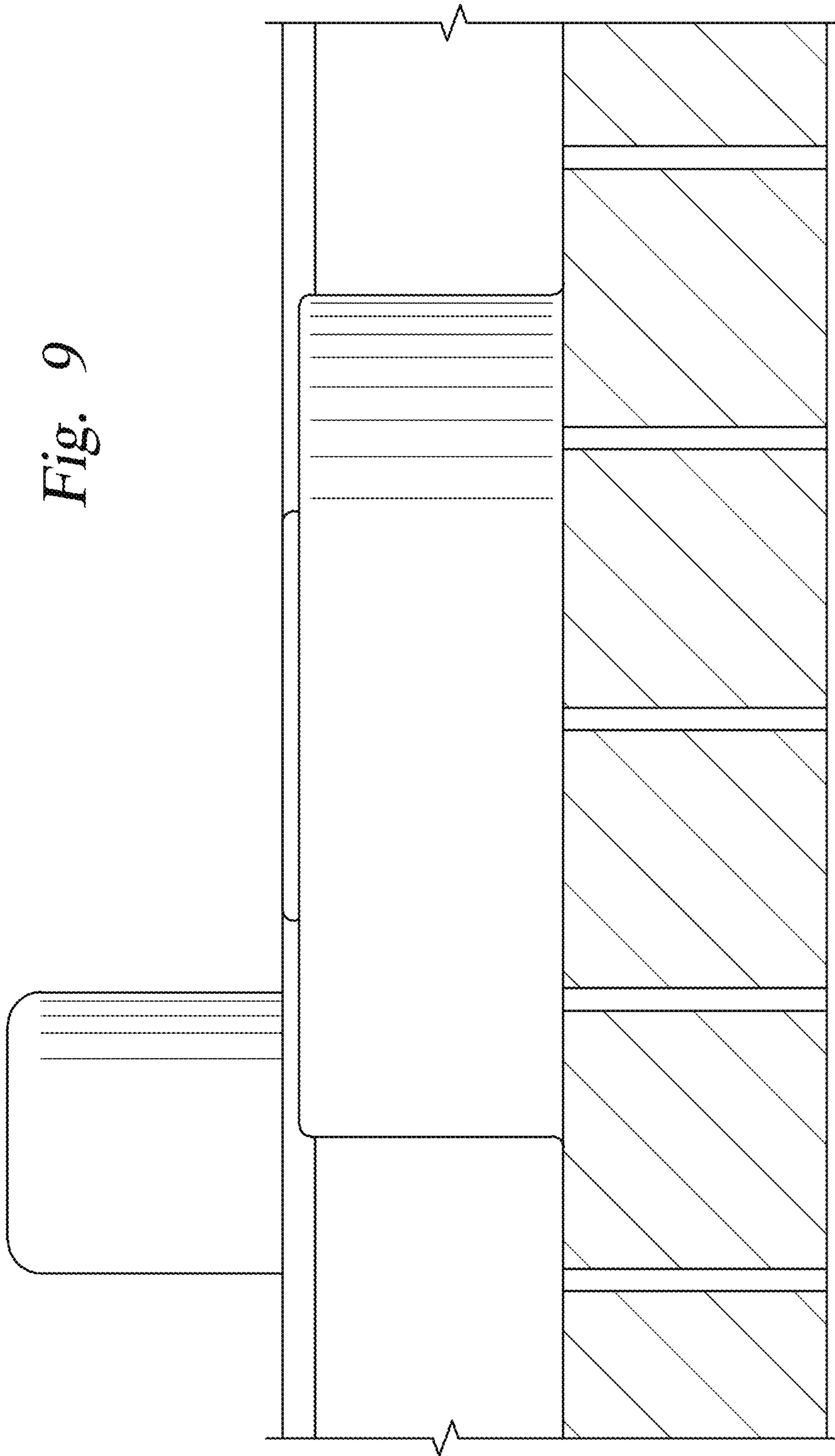


*Fig. 7*



*Fig. 8*

Fig. 9





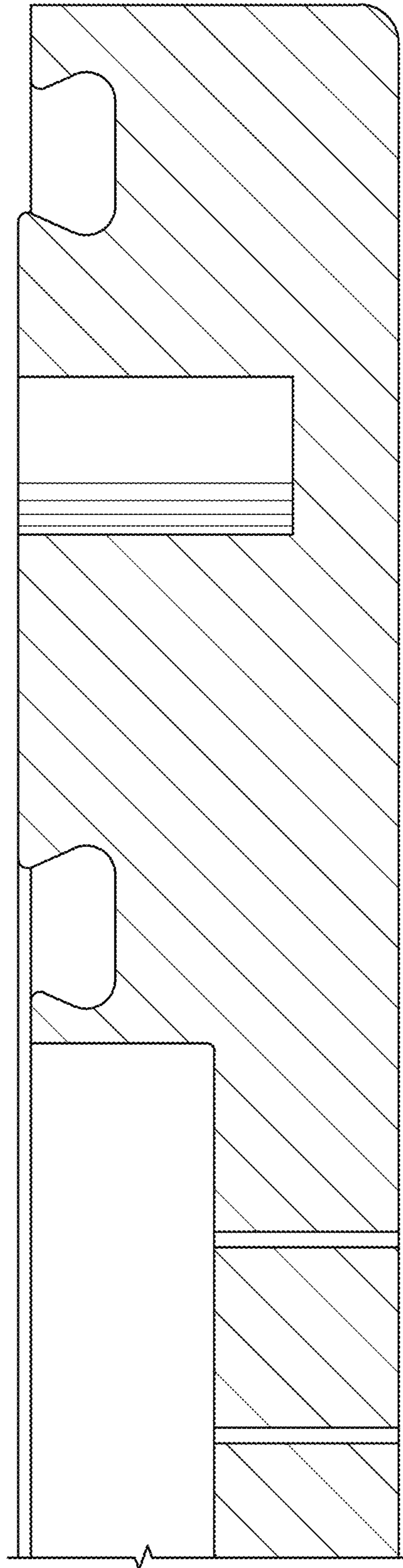


Fig. 10

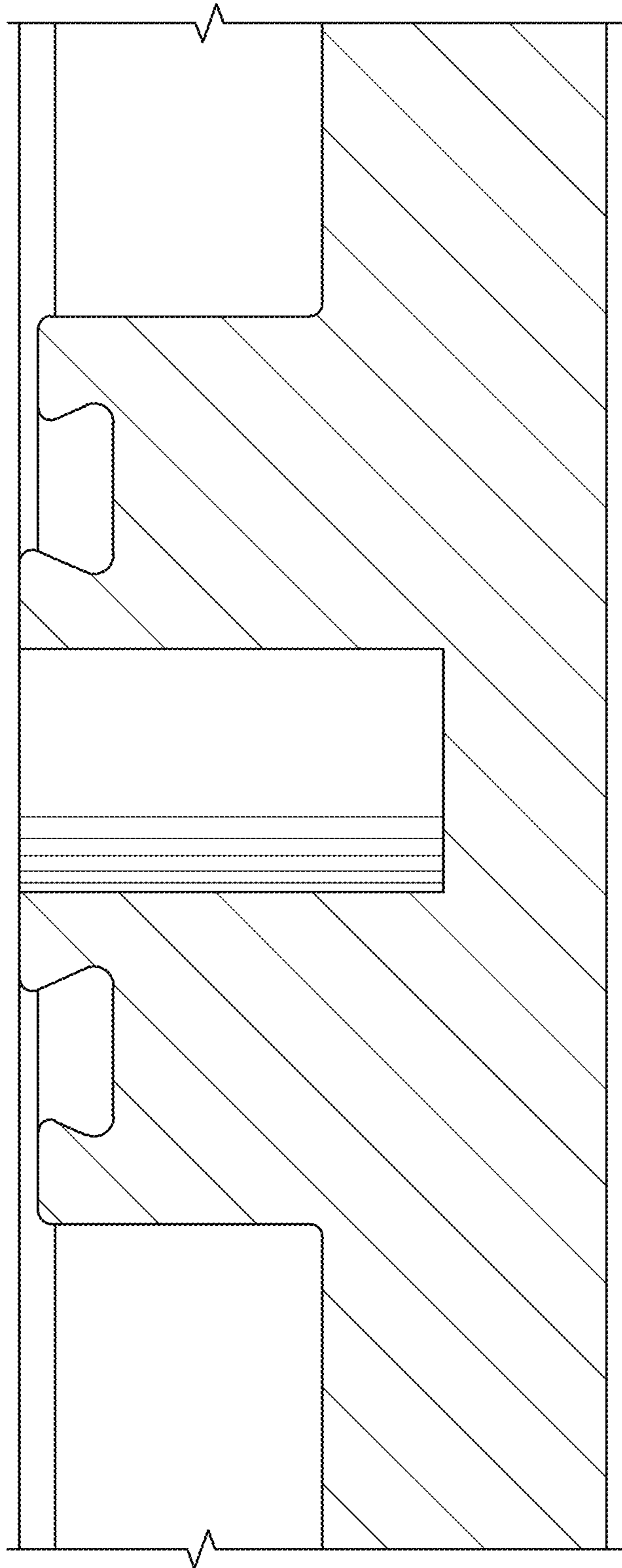


Fig. 11